Controlled hydrothermal growth of vertically-aligned zinc oxide nanowires using silicon and polyimide substrates

Citation for published version:

Digital Object Identifier (DOI):
10.1016/j.mee.2015.03.039

Link:
Link to publication record in Edinburgh Research Explorer

Document Version:
Peer reviewed version

Published In:
Microelectronic Engineering

General rights
Copyright for the publications made accessible via the Edinburgh Research Explorer is retained by the author(s) and / or other copyright owners and it is a condition of accessing these publications that users recognise and abide by the legal requirements associated with these rights.

Take down policy
The University of Edinburgh has made every reasonable effort to ensure that Edinburgh Research Explorer content complies with UK legislation. If you believe that the public display of this file breaches copyright please contact openaccess@ed.ac.uk providing details, and we will remove access to the work immediately and investigate your claim.
Controlled hydrothermal growth of vertically-aligned zinc oxide nanowires using silicon and polyimide substrates

Atif Syed*, Michail Kalloudis, Vasileios Koutsos and Enrico Mastropaolo*

School of Engineering, The University of Edinburgh, King’s Buildings, EH9 3JL, Edinburgh, United Kingdom

*Corresponding authors email: a.syed@ed.ac.uk ; e.mastropaolo@ed.ac.uk

Telephone no.: +44-131-650-5651

Keywords: zinc oxide nanowires, hydrothermal synthesis, Ostwald’s ripening, atomic force microscopy.

Abstract

In this paper, hydrothermal synthesis combined with microfabrication techniques is used for growing vertically-aligned ZnO nanowires (NWs) on zinc (Zn) seed layers patterned on silicon (Si) and polyimide (PI). The NWs have shown a hexagonal crystalline structure and vertical orientation. The substrate material together with the hydrothermal precursor concentration has shown to influence the diameter and length of the NWs. Atomic force microscopy and scanning electron microscopy have revealed that the substrate material affects the size of the deposited seeds and therefore the morphology of the NWs which show a diameter in the range 100 – 220 nm and 130 – 400 nm when grown on Si and PI respectively. NWs grown with an optimised concentration of 2 mM are densely packed and vertically-aligned with a consistent uniform distribution on both types of substrates.
1. Introduction

In the past few years, zinc oxide (ZnO) nanostructures have been attracting large attention for energy harvesting applications (solar cells [1], nanogenerators [2]) and sensors (gas sensors [3] and biosensors [4]). Till date, various ZnO nanostructures have been synthesized such as nanorods [5] [6], nanowires [7] [8] [9], nanoplates [10] [11], nanospikes [12], microtubes [13] and nanotubes [14] [15]. In addition, the combination of biocompatibility and piezoelectric properties of ZnO NWs opens new perspectives for biomedical and chemical sensing [16] [17]. The ability to control morphology, dimensions alignment and position of ZnO NWs is crucial for enabling successful and consistent integration into microsystems and for exploiting the NWs’ unique properties in innovative transducers and composite materials [18] [19]. For instance, the NWs’ diameter plays a key role for the enhancement of their fluorescent properties to be exploited for cancer cells detection [20] [21] [22]. Among the various methods available for growing ZnO NWs, hydrothermal growth is the most promising due to the inherent low temperature processing particularly suitable for synthesis on polymers and CMOS integration. Nanoimprint lithography, microcontact printing and e-beam lithography have been used to perform patterned growth on seed layers deposited on silicon [23] [24] [25]. However, these techniques are costly, not directly compatible with patterning on flexible polymer-based substrates and with large-scale production of semiconductor devices. Photolithography has been used successfully to grow ZnO nanorods (NRs) on specific patterns onto silicon substrates and on flat flexible substrates (i.e., Kapton) [26] [27]. Although previous works have shown that different seed layer thickness and seed materials have a direct effect on the morphology of ZnO NWs, additional studies are needed to shed light on the influence of seed layer roughness and of substrate below the seed layer on the NWs’ size and morphology [28] [29].

In this paper, hydrothermal synthesis and microfabrication processes have been used to grow ZnO NWs on precise locations on zinc seed layers patterned on silicon and polymer-on-silicon substrates. The morphology and crystal structure of the NWs grown on the two different substrates and at different precursor concentration has been analysed and compared by using x-ray diffraction, scanning electron microscopy and atomic force microscopy.
2. Theory – hydrothermal synthesis

Hydrothermal synthesis was performed using zinc nitrate hexahydrate ($Zn(NO_3)_2 \cdot 6H_2O$) and HMTA (hexamethylenetetramine, $C_6H_{12}N_4$) mixed in equimolar concentration in DI water. Previous studies have shown that HMTA acts as a buffer contributing to the amount of hydroxide ions available for the synthesis (i.e., HMTA decomposes into formaldehyde when heated) [30]:

$$C_6H_{12}N_4(s) + 10H_2O(l) \rightleftharpoons 6H - C = H - O(g) + 4NH_3^+(g) + 4OH^- \quad (1)$$

$$NH_3(g) + H_2O(l) \rightarrow NH_4(g) + OH^- \quad (2)$$

Furthermore, by increasing the pH of the precursor solution the rate of hydrolysis (formation of $OH^-$ ions) decreases [30]. The $Zn^{2+}$ ions needed for the formation of the $ZnO$ nanostructures are produced from zinc nitrate hexahydrate:

$$2OH^- + Zn^{2+} \rightarrow Zn(OH)_2(s) \quad (3)$$

The resultant hydroxide then reacts with the remaining Zn ions resulting in $ZnO$:

$$Zn(OH)_2(s) \rightarrow ZnO(s) + H_2O \quad (4)$$

HMTA is responsible for the formation of $ZnO$ NWs (reaction described in equation (4)) by restricting the growth of the $ZnO$ nanostructures only on the $<001>$ facet, hence constraining the growth in one direction. Equation (3) describes the supersaturation stage which is a pre-requisite for the crystallisation of the $ZnO$ products. By tuning this stage, either by varying time and concentration of the precursor solution, the morphology of $ZnO$ NWs can be controlled.

3. Materials and methods

3.1. Chemicals

Reagent grade zinc nitrate hexahydrate ($Zn(NO_3)_2 \cdot 6H_2O$, 98% purity) and ACS reagent grade hexamethylenetetramine ($C_6H_{12}N_4$, 99% purity) were purchased from Sigma-Aldrich and were used without any further purification. Polyimide (PI-2545) was purchased from HD Microsystems.
3.2. Microfabrication process

Figure 1 shows the schematic process flow used to grow ZnO NWs on patterned Zn seed layers. Firstly, 3-inch silicon (Si) wafers were cleaned by using acetone, IPA and DI water. The substrates were primed with hexamethyldisilazane (HDMS) while being heated at 60°C for 1.5 min in order to improve the adhesion of the photoresist (PR). 1.5 µm of PR (Figure 1(a)) was spin coated using edge bead removal (EBR) thus ensuring that the PR at the edge of the substrate is even. After soft-baking at 90°C, the substrates were patterned by UV lithography (7 seconds exposure), developed for 1 min, rinsed in DI water and dried with nitrogen gas (Figure 1(b)). Afterwards, an adhesion layer of titanium (Ti) (10 nm) and zinc (Zn) seed layer (300 nm) were deposited using e-beam evaporation (Figure 1(c)). At this point, ZnO NWs were grown hydrothermally on the substrates (Figure 1(d)). In particular, the substrates were immersed in the precursor solution containing zinc nitrate hexahydrate and HMTA mixed in equimolar concentration in DI water. Two different concentrations (2 mM and 20 mM) were used for investigating the influence of precursor concentration on the growth of the ZnO NWs. The solution was stirred at 550 rpm while monitoring the pH throughout the process. Stirring was stopped when the pH reached a saturation point between 6.75-6.85 (5-10 min). Synthesis was carried out for 16-17 hours at 90°C. Once the hydrothermal process was completed, the substrates were cleaned with DI water and dried in air. Afterwards, lift-off was performed thus removing the NWs grown on the Zn/PR/Si while leaving the NWs grown on the Zn/Si (Figure 1(e)).
In order to investigate the possibility of growing ZnO NWs on polymer films, the process described above was modified to include the deposition of a thin film of PI on top of Si substrates (PI/Si). In this case, before coating the substrates with PR, 1.7 µm of PI were spin-coated and cured by increasing the temperature at 4°C/min up to 200°C for 1 hour (Figure 1(a)).

3.3. Measurements
The crystalline properties of the nanostructures grown on both Si and PI/Si substrates were investigated using x-ray diffraction (XRD) (Bruker D8 Advance in Bragg-Brentano configuration). The morphology and geometry of the nanostructures were investigated using scanning electron microscopy (SEM). Further investigations on the structures morphology were carried out by atomic force microscopy (AFM) (Bruker Multimode 5). AFM scans were performed in tapping mode and using Bruker MPP-11100-10 tips (nominal spring constant in the range 20-80 N/m and tip radius of about 12 nm).

4. Results and discussion
Vertically aligned ZnO NWs were successfully synthesized on the patterned Zn seed layers. The synthesis was carried out using two different concentrations (2 mM and 20 mM) on Si and PI/Si in order to investigate the influence of substrate material and precursor concentration on the diameter of ZnO NWs.

4.1. Crystal structure
XRD was performed on the nanostructures grown on Si and on PI/Si. Figure 2 shows the XRD spectra obtained for ZnO NWs grown on bare Si and on PI/Si. In both cases, a very sharp peak is observed at 2-theta = 35 deg. which is associated to the (002) crystalline orientation thus indicating that the ZnO NWs are single crystalline and vertically-oriented in the c-direction. The peak observed at 2-theta ~ 36 deg. is associated to the (002) plane of the Zn seed layer. The much lower amplitudes of the peaks associated to the Zn seed with respect to the peak associated to the ZnO NWs indicates that most of the Zn layer was utilised for the growth. Other peaks associated to the Ti adhesion layer, native oxide, titanium nitride (TiN) and other planes of ZnO are observed and indicated in Figure 2. The obtained XRD spectra show identical characteristics for NWs grown on Si and PI/Si thus proving that the developed process allows synthesising single crystalline and vertically-oriented ZnO NWs regardless the substrate used.
4.2. Influence of substrate material

SEM and AFM were used to investigate the height, surface morphologies and diameter of the ZnO NWs. Figure 3 shows the SEM and AFM micrographs of ZnO NWs grown using 2 mM as precursor concentration on the Zn seed layer patterned on Si substrates (Figure (a)) and on PI films on Si (PI/Si) (Figure 3(b)). From Figure 3, it can be seen that the ZnO NWs grown on Si substrates are dense and tightly packed and have more even distribution compared to the ones grown on PI/Si substrates. It is worth pointing out that the NWs are densely distributed and the distinction between a single nanowire and a cluster of nanowires is relatively challenging due to the finite size of the AFM tip apex.

Particle-size distribution analysis was performed in order to estimate accurately the diameter and the diameter distribution of the NWs. When grown on Si substrates, the obtained NWs have a diameter in the range 100 nm – 220 nm with average of 130 nm (SD 40 nm) while, when grown on PI/Si, the NW’s diameter increased towards higher values in the range 130 nm – 400 nm with average of 265 nm (SD 145 nm). The larger diameter and broader diameter distribution observed when PI/Si substrates were used is most likely due to the intrinsic polymer characteristics of the PI layer under the Zn seed layer. AFM measurements performed on the Zn seeds after evaporation on Si and on PI/Si revealed RMS roughness values ~31 nm and ~43 nm, respectively, thus showing an increase of about 27% in seeds’ roughness on the PI/Si substrate. Furthermore, particle-size distribution analysis showed a higher average for grain diameters when depositing the Zn seeds on PI/Si (572 nm, SD 65 nm) compared to...
the ones on Si (407 nm, SD 96 nm). In addition, it is believed that the surface interactions between the Zn layer and PI layer are affected by the temperature increase experienced during the hydrothermal process. Under these conditions, a larger amount of Zn ions are required to initiate the NWs growth from the Zn seed thus resulting in an increase of the overall NWs diameter.

![SEM and AFM images of ZnO NWs grown using 2 mM concentration (a) on Si and (b) on PI/Si](image)

Figure 3: SEM and AFM images of ZnO NWs grown using 2 mM concentration (a) on Si and (b) on PI/Si

Figure 4 show the simultaneously acquired phase shift and amplitude images, respectively. The contrast in the phase image is mainly due to topographical effects (single or clustered NWs’ edges); otherwise there is no significant contrast thus indicating that the NWs have same chemical composition. The amplitude image emphasises even more the edges of the features (irrespective of their height level) and indicates that the NWs are of similar lateral size. From the AFM analysis, the mean height of ZnO nanowires grown on Si and PI/Si showed distribution with a kurtosis of 3.275 indicating Gaussian-type distribution and skew of 0.0517 indicating that the size of the NWs is distributed symmetrically with respect to the average value. ZnO NWs on PI/Si showed height distribution with a kurtosis of 3.09 and skew 0.31 indicating Gaussian-type distribution but distributed relatively unsymmetrically with respect to the average value.

![AFM images](image)
4.3. Influence of precursor concentration

Figure 5 shows the SEM micrographs of ZnO NWs grown at the precursor concentration of 20 mM on Si substrates. It is observed that by increasing the concentration by a factor of 10 (from 2 mM to 20 mM), the ZnO NWs diameter and length increase from about 150 nm to 1 µm and from 1.1 µm to 6 µm, respectively. Table 1 summarises the results obtained in this and other works in literature using similar precursor concentrations [29] [30]. Although, the increase of diameter and length as a function of precursor concentration is in agreement with the other works, the size and the size increase are much larger most likely due to differences in seed layer thickness and seeds diameter. A closer look at Figure 4 shows that Ostwald’s ripening occurs when using high precursor concentration. In particular, from the inset of Figure 4, ZnO NWs having small diameter (~ 200 nm) can be seen next to thick ZnO NRs with larger diameter (~ 1 µm) due to Ostwald’s ripening which is observed in solutions where larger particles (nanostructures) grow at the expense of smaller particles [31]. The unstable molecules at on the surface of the Zn seed dissolve thus shrinking the size of the seed and therefore the number of free molecules within the solution increases due to the higher precursor concentration. During supersaturation stage (equation (3)), the free molecules deposited close to larger Zn seeds should dissolve. However, due to the presence of HMTA, which forces the growth in one direction, the free molecules do not dissolve hereby forming ZnO NWs next to ZnO NRs. Based on these observations, the growth of thinner NWs arising from Ostwald’s ripening can be reduced by increasing synthesis time and/or adjusting HMTA concentration.
Vertically aligned ZnO NWs were grown on patterned Zn seed layers on Si and PI/Si substrates. The process presented allows growing ZnO NWs on specific locations on the substrates with micrometric accuracy. ZnO NWs grown on both Si and PI/Si substrates showed a clear hexagonal structure with a crystalline orientation in the (002) direction. By controlling the concentration of the precursor solution and also maintaining a constant pH, high quality, tightly packed and vertically aligned ZnO NWs were synthesized.

The substrate showed to play a key influence on the NWs’ morphology. In particular, the measured diameter and diameter distribution of NWs grown on PI/Si was observed to be much larger compared to the case of growth on Si. The larger diameter and diameter range is most likely due larger grain size of the seeds on the polymer substrates (grain diameter and roughness were 28% and 27%, respectively,
higher than the ones measured for the seed layers deposited on Si). In consistent agreement with other works, the precursor concentration has shown to influence the NWs’ diameter. In particular, an approximate 5-fold increase in NWs’ diameter was achieved with a 10-fold increase of precursor concentration. Using the combined microfabrication process and chemical synthesis presented in this work, ZnO NWs can be grown on different substrates (including polymer substrates) at low temperatures (< 100° C). The presented results give insight on the control and optimisation of ZnO NWs growth for large-scale fabrication on different substrates with high reproducibility. The method presented can be used to grow ZnO NWs on polydimethylsiloxane (PDMS), Kapton films and other flexible polymers. The ZnO NWs synthesised in this work can be used for application in biomedical sensors, novel transducers, smart materials, nanogenerators and drug delivery systems.
References


